Business matching room



Catalogs of products for business matching Commercialization of developed equipment (ALD, bonding, CATCVD)



Samples for packaging (Tanaka Kikinzoku Kogyo, NGK, Nikko)

Hands-on access fab.



Nanoimprint, Sandblust, Water laser



Each process steps in the wafer fabrication



MEMSAS Ltd. (Minimal invasive medicine)



Sightseeing information of Sendai city



MEMS Core Co. Ltd. (Contract development of MEMS)



MEMS company map in Tohoku resion

1 Hands-on-access fab. (Prof. K. Totsu)

Shared facility for industry to prototype MEMS devices (4 / 6 inch). Companies which cannot prepare their own facility dispatch their employees to operate equipments by themselves. The facility is located in 1800m² clean room, which was used for the production of power transistor and newly installed MEMS fabrication equipments. <u>http://www.mu-sic.tohoku.ac.jp/coin/index.html</u>

Contact person: Professor Kentaro Totsu Phone 022-229-4113, totsu@mems.mech.tohoku.ac.jp



Transition of income and expenditures

Transition of user number

2 Hands-on-access fab. Equipment



FIR

~3"

SI SMIS200

AFM

~8"

Digital Instruments

Thermal imprinting ~50mm

Origin electric Reprine-T50A MAX 650°C, 30kN TOF-SIMS

CAMECATOF-SIMS IV

HALL F PIL - Ur 2 PE-CVD ~8" 熱CVD PE-CVD ~6 ~6 tomo MPX-CVD SiN, SiO₂ JPEL VDS-560 Epi-Poly Poly-Si, 1100°C SiN, SiO₂ 1 41 11. • 8 200 Sputtering Sputtering Sputtering ~6" ~8" ~8" Anetva SPF-730 8inch target x3 Ai, AISi Shibaura 1-Miler htarget x 4, Load lock, atic transfer x 10 wafe Shibaura CFS-4ESI 3inch target x 3 ge cooling x1, heating 3mcl Automatic sol-gel deposition ~4" EB evaporation MOCVD ~6' ~8" Wacom Doctor-T PZT, up to 8inch Anelva EVC-1501 Technofine PZ-604 199 調視 i a -----Chemical dry etcher (CDE) ALD ~6" ICP-RIE ~6" ~4" Technofine ALK-600 ULVAC NE-550 Shibaura CDE-7 -1-Dry etcher ~6" Dry etcher 4" AI RIE 4 Anelva DEA-506 For SiN, SiO2 etching Anelva L-507DL For Si etching Shibaura HIRRE-100 Cl₂, BCl₃ de 1 · 111 JFL 1 . A ECR etcher KOH- TMAH -6" Vapor HF 3 -8" Anelva ECR6001 3 inch GaAs, AlGaN, etc. omo Primaxx uEtch -2 50 Film thickness Surface profiler Wafer dust counter measurement ~6 ~6 ~6" Nanometric lanoSpec 3000 Dektak8 ~ AinhaStep 500 Topcon WM-3 A 意 有量 4 (°)-IR microscope 4-terminal probe Spreading resistance measurement ~6 ~6" Solid State Measurements Olympus, Hamar - ma M SEM FE-SEM Digital microscope -8" ~12" Chip Keyence and Kunoh Hitachi S3700N Hitachi S5000 EDX -14 Ultrasonic Line-focus-beam Ellipsometry X-ray micro CT acoustic microscope ~6" ~6' ~12" microscope Photonic lattice SE-101 ULVAC Comscantechno ScanXmate D160TS110 Insight IS350

MEMSAS Inc. 3

MEMSAS Inc. \rightarrow Products (sensors and actuators based on MEMS) →Technical support MEMS foundry Tohoku University MEMSAS Inc. Semiconductor Biomedical Engineering fabrication process (MEMS Actuator and Sensor)



MEMSAS,INC. is the venture company on the purpose of application development, manufacturing consulting, and sales for sensor and actuator which are fabricated based on MEMS(Micro Electro Mechanical Systems) technology. We have developed the tip of catheters equipped with small movement mechanism for minimally invasive instruments that performs inspection and medical treatment safely by controlling the movement and micro pressure sensor(which is very thin like hair) from outside. By applying small movement mechanism, we also have developed 2-Dimensional tactile display (Pin Display) for visually impaired persons. Concerning basic research and development, we actively utilize the research environment of Tohoku University by conducting an animal experiment and evaluating the trial production for medical instruments in Graduate school of Biomedical engineering, Tohoku University.

About MEMSAS

Name :	MEMSAS Inc.
	http://www.memsas.co.jp
Established :	September 29th, 2004
Location :	#1003, 1-6-22, 1 ban-cho Aoba-ku Sendai-shi Miyagi, Japan, 980-0811
Board	Representative director: Kazuya Kato
Members :	Director: Masayoshi Esashi, Yoichi Haga, Tadao Matsunaga, Kentaro Totsu
	Corporate auditor: Nobui Mishina

Products

Sensors based on MEMS



Ultra-thin fiber optic pressure sensor UITRA-THIN TIDEF OPTIC DRESSURE SERISOF For the purpose of local pressure neasurement in a very narrow space, ultra-treatment. Bending mechanism utilizing miniature fiber-optic pressure sensor of 125µm in diameter has been developed. Thin diaphragm which is bonded at a tip of the optical fiber is deformed by applying a pressure, and the deformation changing is measured interferometricallyeasy. In particular, fiber-optic pressure sensors have the advantages of not only high potential of miniaturization but also applicability to use in such electromagnetically harsh environments as in an operating room in a hospital.



Active bending mechanism for ileus tubes

Ileus tube is used for the ileus treatment. Bending mechanism utilizing



Active bending electronic endoscope

For inspection and treatment For inspection and treatment inside of the small intestine Disposable endoscope has been developed by combining small electrical imager and bending mechanism using SMA actuator.



2-D tactile pin display Two-dimensional tactle prim display has been developed for visually impaired people. Character and graphic information is dynamically displayed by an array of pins in up and down positions. The contraction of SMA micro-eoil actuators moves the pins up and down, and latch mechanism using a permanent magnet accurately positions the pins in an up or down state without any feedback control.

Contact Yoichi Haga, haga⊜toboku.ac.jp Tadao Matsunaga, matsunaga@toboku.ac.j Graduate school of biomedical eng Tohoka University



Process Menu at MEMS-CORE

item	Process	Material/Equipment			
Film deposition	Dielectrics (SiO ₂ , NSG, PSG)	Oxidation furnace, P-TEOS Atmospheric Pressure-CVD			
	Metal (Au, Pt, Cr, Ti, Cu, W <i>et a</i>)	Sputtering, EB evaporation, Electro-plating			
Photo-lithography	Resist Coat /Bake Exposure	Spin coater, Bake oven, Hot-plate Sus MA6, Double side aligner,			
	Photomask making	CAD (CoventorWare™), Pattern generator			
Etching	Dry etching (SiO ₂ , Si, Metals)	Deep RIE, RIE, Sacrificial Etching, XeF ₂ Siletching Ion milling, O ₂ plasma asher			
	Wet etching	TMAH, HF-NH ₄ F, Metal wet etching			
Bonding	Wafer bonding	Anodic bonding, Thermal bonding			
Dicing Packaging	Wafer dicing	Blade dicer, Leaser dicer(Stealth)			
	Die bonding, Wire bonding	Die bonder, Wire bonder			
Polishing	Wafer polishing	Chemical mechanical polisher, Cleaner			
Measurement Inspection		Measurement microscope, Leaser microscope, SEM, Stress monitor Sheet resistance, Surface profiler, Optical thickness measurement			
Miscellaneous	Cleaning, Surface treatment	UV/0, HMDS			

Foundry service/Collaboration scheme

]	Concept	Design	Proto type	Evalua tion	Production	Example
MEMS-CORE original						Acoustic emission sensor
Contracted development				*	*	
Collaboration	*	*		*	*	
Contracted production				*	*	
Opera	ted by Custom	er	. Men	IS-CORE	🖈 :Case b	y case
	RE Co. Ltd., //www.mema				mems-core.α 777-8717 FA	om X:+81-22-777-8718

MEMS company map in Tohoku region

Micronics Japan Co.Ltd (Hirakawa) Probe card

Akita Adamant Co. Ltd (Yokote) Optical MEMS

Akita Epson Co. Ltd (Yuzawa) Ink jet print head

<u>Ahiko Finetech Co. Ltd.</u> (<u>Shinjo)</u> Glass micromachining, Thin film

Kyowa Electronic Instruments Co. Ltd (Higashine) Strain gauge

Chino Corp. (Tendo) Infrared sensor, Gas sensor

Techno Morioka Co. Ltd (Nagai) Water quality indicator, Flow sensor

<u>E • M • C Semiconductor</u> Corp (Date) Optical sensor

ARS Co. Ltd(Motomiya) MEMS packaging Tamagawa Seiki Co. Ltd (Hachinohe) Piezoelectric gyro

FTC Corp. (Morioka) MEMS contract development

Lightom (Morioka) MEMS contract development

RICOH Industrial Solutions Inc (Hanamaki) Optical MEMS

Kuramoto Co. Ltd (Ichinoseki) Flow sensor, MEMS foundry service

> ALPS Electric Co. Ltd (Ohsaki) Pressure, Vibration, Magnetic, Force sensors

TDC Corp (Rifu) Precise polishing

MEMS Core Co.Ltd(Sendai) MEMS contract development

MEMSAS Inc(Sendai) MEDICAL sensors, actuators

Sendai Smart Machines Co., Ltd (Sendai) Sensor nerwork

Advantest Component Inc. (Sebdai) Probe card, MEMS foundry service

Technofine Co, Ltd (Sendai) Equipments for MEMS

RICOH Co. Ltd (Natori) Optical MEMS

TOKIN Corp. (Shiroishi) Piezoelectric MEMS

Munekata Co. Ltd (Fukushima) Micro fluidic device for analysis



Advantest Laboratories Ltd. Advantest Component Corp. Advantest Technologies Co., Ltd. Ahiko Finetec Co., Ltd. ALPS ALPINE CO., LTD. EV Group Japan KK Ushio Inc. SPP Technologies Co., Ltd. Orbray Co., Ltd. Koken Ltd. Citizen Watch Co., Ltd. SHIBAURA MECHATRONICS CORP. SCHOTT Japan Corp. Sumitomo Precision Products CO., LTD. Fujikura Kasei Co., Ltd. Tsuken Electric Ind. Co., Ltd. TDC Corp. TECNISCO, LTD. Tokyo Electron Ltd. TOKYO PHKA KOGYO CO., LTD. TOKYO KFIKI INC Tohoku Economic Federation NAITO SENSEI KOGYO CO., LTD.

Nagase & Co., Ltd. Nabtesco Corp. NAMICS CORP. NIDEC COMPONENTS CORP. Nippon Kayaku Co., Ltd. Nippon Signal Company Ltd. Nihon Dempa Kogyo Co., Ltd. Niterra Co., Ltd. PARKER CORP. Panasonic Industry Co., Ltd. Hamamatsu Photonics K.K. Hitachi High-Tech Corp. FUJI ELECTRIC CO., LTD. HOKURIKU ELECTRIC INDUSTRY CO., LTD. Mitsubishi Electric Corp. Murata Manufacturing Co., Ltd.